

**AMENDMENTS TO THE CLAIMS**

a1

1. (currently amended) An arc chamber of an ion implanter system comprising:  
an arc chamber enclosure for an electron emissive source, said source extending  
into said arc chamber enclosure through a wall of said arc chamber enclosure, said wall  
through which said source extends comprising an alumina insulator material surrounding  
said source.

2-4. (canceled)

a2

5. (currently amended) The arc chamber of Claim 1 wherein a substantial  
portion of said wall through which said source extends into the arc chamber comprises an  
said alumina insulator material.